

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3105	(substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 15:37
S2	1123	(substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3) and (chamber or tank) same (hold\$3 or plate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:00
S3	609	(substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4) and (fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:00
S4	143	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:02
S5	32	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horiztonal\$4 or side or lateral or swirl\$3 or spin\$4 or flowing) with (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:18
S6	1111	134/200	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:10

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S7	8	S5 and "134".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:17
S8	85	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horiztonal\$4 or side or lateral or swirl\$3 or spin\$4 or flowing) with (spray\$3 or nozzle or discharg\$3 or dispos\$3 or side) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:15
S9	19	S8 and "134".clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:17
S10	17	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horiztonal\$4 or side or lateral or swirl\$3 or flowing) with (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:19
S11	24	(fluid or liquid or solution) near10 ((high near2 pressure) or (pressure adj (vessel or chamber))) and (horiztonal\$4 or side or lateral or swirl\$3 or angled or angling or angle) with (spray\$3 or nozzle or discharg\$3 or dispos\$3) same (chamber or tank) same (hold\$3 or plate) same (substrate or semiconductor or wafer or semi\$1conductor) same (rotat\$3 or spin\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:20
S12	2	"6096100".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 10:50

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S13	248	muraoka adj yusuke.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 15:37
S14	76	S13 and pressure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 15:40
S15	29	S14 and mix\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 16:17
S16	18	S14 and mixing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 16:24
S17	3	"6306564".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/18 16:24